

Patent Attorney's Docket No. <u>015290-238</u>

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Pat	ent Application of)					
Jeffrey HUNG et al.			Group Art Unit: 1765				
Application No.: 09/002,007			Examiner: L. Vinh				
Filed: De	ecember 31, 1997)					
	ETCHING PROCESS FOR ORGANIC ANTI-REFLECTIVE COATING)))					
	AMENDMENT/REPLY T	'RAI	NSMITTAL LETTER				
	t Commissioner for Patents ton, D.C. 20231			÷			
Sir:							
Enc	losed is a reply for the above-identified pa	atent	application.				
[]	A Petition for Extension of Time is also	enc	losed.				
[]	requisite Government fee are also enclosed						
[]	Also enclosed is						
[]	Also enclosed is						
[]	Applicant(s) request continued examina the[] \$355.00 (279) [] \$710.00 (179) fee		under 37 C.F.R. § 1.114 and enclose				
	[] Applicant(s) previously submitted requested.	, ·	on, for which continued examination is				
[]	A Request for Entry and Consideration (146/246) is also enclosed.	of S	ubmission under 37 C.F.R. § 1.129(a)				
[x]	No additional claim fee is required.						

[] An additional claim fee is required, and is calculated as shown below:

		AMENDED	CLAIMS	⊕	
	No. OF CLAIMS	HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	ADDT'L FEE
Total Claims	20	MINUS 20 =	0	× \$18.00 (103) =	0.00
Independent Claims	3	MINUS 3 =	0	× \$80.00 (102) =	0.00
If Amendment adds mu	ıltiple depende	ent claims, add \$270	0.00 (104)		
Total Amendment Fee					
If small entity status is	claimed, subt	ract 50% of Total A	mendment Fe	e	
TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT					0.00

	A	claim	fee in	the	amount	of S	<u> </u>	is enclosed	٠.

[] Charge \$_____ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R.

§§ 1.16, 1.17, 1.20(d) and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

Burns, Doane, Swecker & Mathis, L.L.I

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Date: October 13, 2000



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AMENDMENT

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Official Action dated July 13, 2000, please amend the aboveidentified application as follows.

REMARKS

Favorable reconsideration of this application in light of the following remarks is respectfully requested.

The present invention broadly relates to etching an organic anti-reflective coating (ARC). In particular, the present invention sets forth a process for removing exposed areas of an organic ARC on a metallic layer, the exposed areas of the ARC having been exposed by previously etching a photoresist covering the ARC. The process comprises exposing the exposed areas of the ARC to an oxygen-free system of etching agents in an ionized state in